Class SSUE CLASS		*			
	U.S., UT I	ILITY Paten	t Applicat	ion	
	SCANNER	O.I.P.E.	, G	ATENT DATE	
APPLICATION NO. CO	ONT/PRIOR CLASS	SUBCLASS	ART UNIT	EXAMINER	i de la companya de l
09/574653	257438	199	272	H. V	ee
Youngmin Kim Shawn Walsh	1			V	
APPLIC	٠.				
と、花を作品できない。 と 、出	dewäll spacer ;	process fo	cmos i	ntegrated (circuits
E				A	. PT
ORIGINAL	ISSUIN	IG CLASSI		V. A.	1
Company of the Compan	IBCLASS CLASS	S SUE		ERENCE(S) SUBCLASS PER	R BLOCK)
			r.h.k		
MIERNA WONAL CLAS	SIFICATION				
		SAPPE STATE	L.	ontinued on Issue S	lip Inside File Jacke
					The state of the s
TERMINAL DISCLAIMER	Sheets Drwg.	DRAWINGS:	Print Fig.	CLAN	MS ALLOWED
The term of this patent				NOTICE OF AL	LOWANCE MAI
subsequent to has been disclaimed.	(date) (Assistant	t Examiner)	(Date)		
The term of this patent s		4,			
of U.S Patent. No.		0		Amount Due	SUE FEE Date Pa
	(Drimon)	Examiner)	(Date)		
The terminalmonths			7	SSUE BA	TCH NUMBER
this patent have been disclain	med.	nents Examiner)	(Date)		